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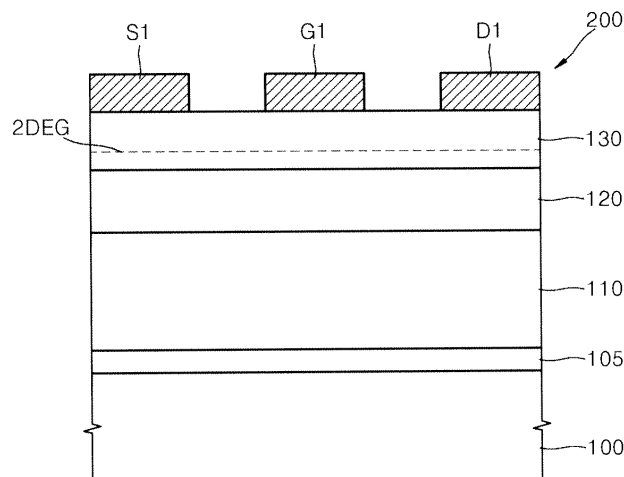
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(54) **Gallium Nitride Based Semiconductor Devices and Methods of Manufacturing the Same**

(57) Gallium nitride (GaN) based semiconductor devices and methods of manufacturing the same. The GaN-based semiconductor device may include a heat dissipation substrate (that is, a thermal conductive substrate); a GaN-based multi-layer arranged on the heat dissipation substrate and having N-face polarity; and a heterostructure field effect transistor (HFET) or a Schottky electrode arranged on the GaN-based multi-layer. The HFET device may include a gate having a double recess structure. While such a GaN-based semiconductor device is being manufactured, a wafer bonding process and a laser lift-off process may be used.

ture field effect transistor (HFET) or a Schottky electrode arranged on the GaN-based multi-layer. The HFET device may include a gate having a double recess structure. While such a GaN-based semiconductor device is being manufactured, a wafer bonding process and a laser lift-off process may be used.

**FIG. 1**





## EUROPEAN SEARCH REPORT

Application Number  
EP 11 18 0488

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Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (IPC)
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Y	* paragraph [0064] - paragraph [0093]; figures 29-45 *	4,5,11	
Y	US 2010/155741 A1 (OHKI TOSHIHIRO [JP] ET AL) 24 June 2010 (2010-06-24) * figure 2 *	4	
Y	US 2010/140660 A1 (WU YIFENG [US] ET AL) 10 June 2010 (2010-06-10) * abstract; figure 4 *	5,11	
X	US 2009/267188 A1 (PINER EDWIN L [US] ET AL PINER EDWIN LANIER [US] ET AL) 29 October 2009 (2009-10-29) * the whole document *	1,2,6, 8-10, 12-14	TECHNICAL FIELDS SEARCHED (IPC)  H01L
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A	YI-FENG WU ET AL: "Very-High Power Density AlGaIn/GaN HEMTs", IEEE TRANSACTIONS ON ELECTRON DEVICES, IEEE SERVICE CENTER, PISCATAWAY, NJ, US, vol. 48, no. 3, 1 March 2001 (2001-03-01), XP011017552, ISSN: 0018-9383 * the whole document *	1-15	
The present search report has been drawn up for all claims			
Place of search The Hague		Date of completion of the search 24 June 2013	Examiner Baillet, Bernard
<p>CATEGORY OF CITED DOCUMENTS</p> <p>X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document</p> <p>T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons &amp; : member of the same patent family, corresponding document</p>			

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**ANNEX TO THE EUROPEAN SEARCH REPORT  
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This annex lists the patent family members relating to the patent documents cited in the above-mentioned European search report.  
The members are as contained in the European Patent Office EDP file on  
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